



# Polishing Slurry

PRODUCT CODE

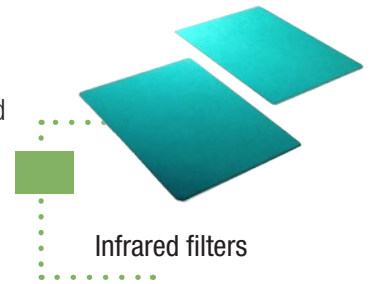
## BG SERIES

**BG series** polishing slurry was developed for polishing IR cutoff filters used for camera lenses.

**BG-50** slurry achieves more than 2 times polishing removal rate and superior surface finish compared with Cerium oxide polishing.

**BG-100F** 2<sup>nd</sup> step slurry is used for high end quality filters.

### Main applications



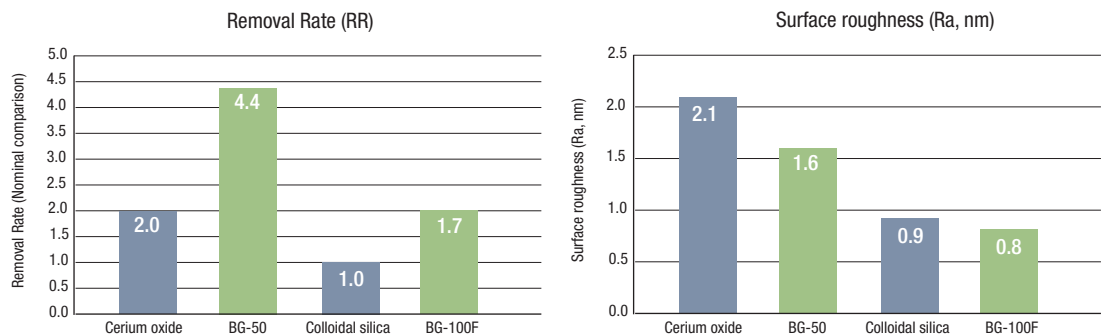
## POLISHING CONDITION

Machine	φ 380 mm single side
Plate rotation	50 rpm
Down force	100 g / cm <sup>2</sup>

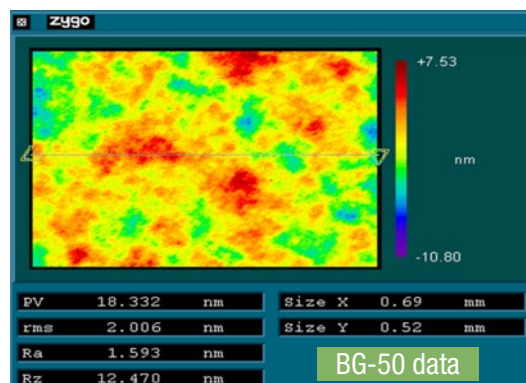
### Advantage of RR and roughness

More than 1.5 times polishing removal rate is achieved and obtains comparable surface roughness with traditional colloidal silica.

Polishing operation by the combination of **BG-50** and **BG-100F** slurry assure improvement of productivity and surface quality.



### Surface roughness (Zygo New View)



## SLURRY FORMULATION

Products	D50(μm)	pH	Dilution
BG-50	0.25	10 - 12	1 : 3
BG-100F	0.15	10 - 12	1 : 4

Typical values are given by Baikowski as an indication only. Such values are not contractual.

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